

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2001-345303

(43)Date of publication of application : 14.12.2001

(51)Int.Cl.

H01L 21/304

C11D 3/26

C11D 7/32

(21)Application number : 2001-099151

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(22)Date of filing : 30.03.2001

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(30)Priority

Priority number : 2000094715 Priority date : 30.03.2000 Priority country : JP

(54) METHOD FOR PROCESSING SURFACE OF SUBSTRATE

(57)Abstract:

PROBLEM TO BE SOLVED: To provide such a cleaning method that satisfies three requirements, i.e., (1) no corroding of transition metal or transition metal compound and barrier metal, (2) superior removal of particle contamination on the surface of a substrate, and (3) superior removal of metallic contamination on the surface thereof, during cleaning of the substrate which has a transition metal or a transition metal compound on its surface.

SOLUTION: This method uses a surface processing agent which contains an organic alkaline and a complexing agent, and further a surfactant, and it is used to clean a substrate having a transition metal or a transition metal compound on its surface.

LEGAL STATUS

[Date of request for examination] 16.08.2004

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the
examiner's decision of rejection or application converted
registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of
rejection]

[Date of extinction of right]

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